



Edge Functionalization and Doping Effects on Stability, Electronic and Magnetic Properties of Silicene Nanoribbons

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Electronic Supplementary Information

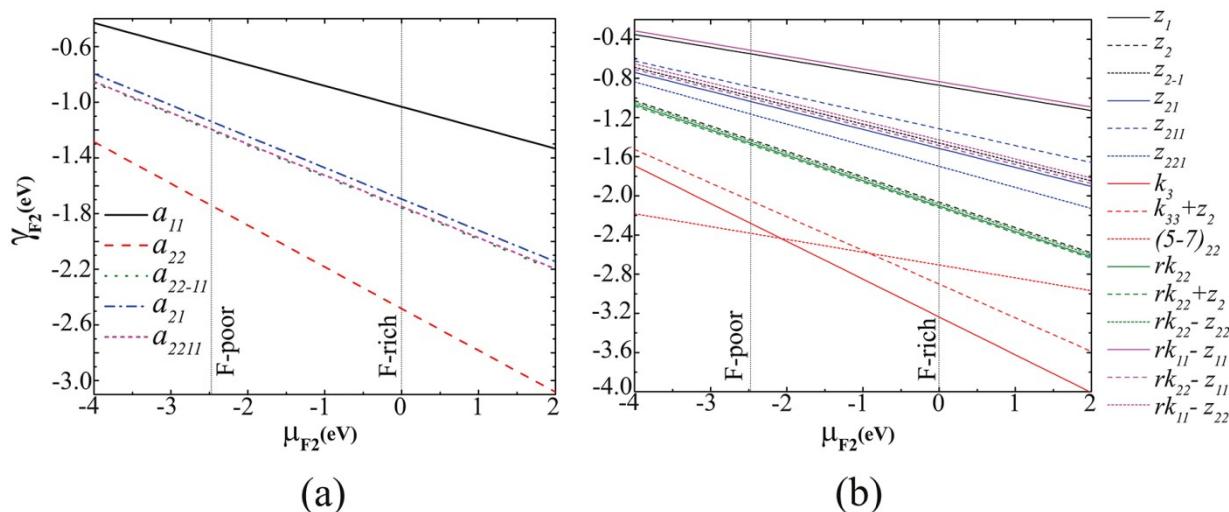


Fig. S1 (a) Edge free energy γ_{F2} as a function of fluorine chemical potential μ_{F2} , using E_{F2} as the zero reference, for (a) different fluorinated edge ASiNRs (b) different edge structures of fluorinated SiNRs along $<2\bar{1}\bar{1}0>$. The allowed range for fluorine chemical potential is indicated by vertical dotted lines.

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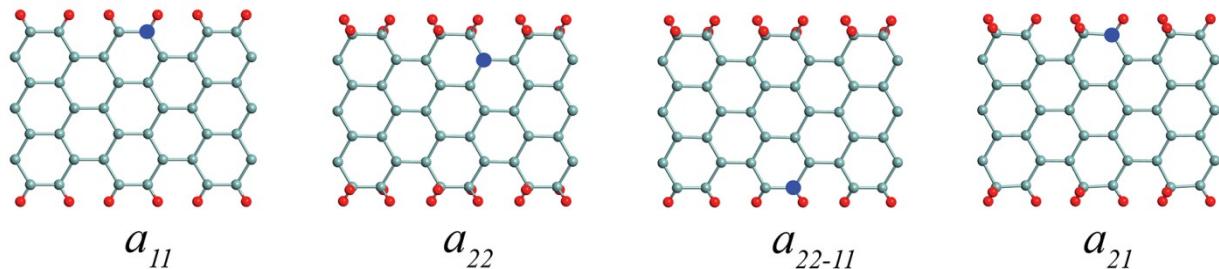


Fig. S2 Schematic structural models of the different edge functionalized ASiNRs doped with a N or B atom, in which the most stable substitution configurations are indicated. The cyan and red balls represent Si and functional addends (H, F, Cl, Br, and I), respectively, and the blue solid circle shows a N or B atom.

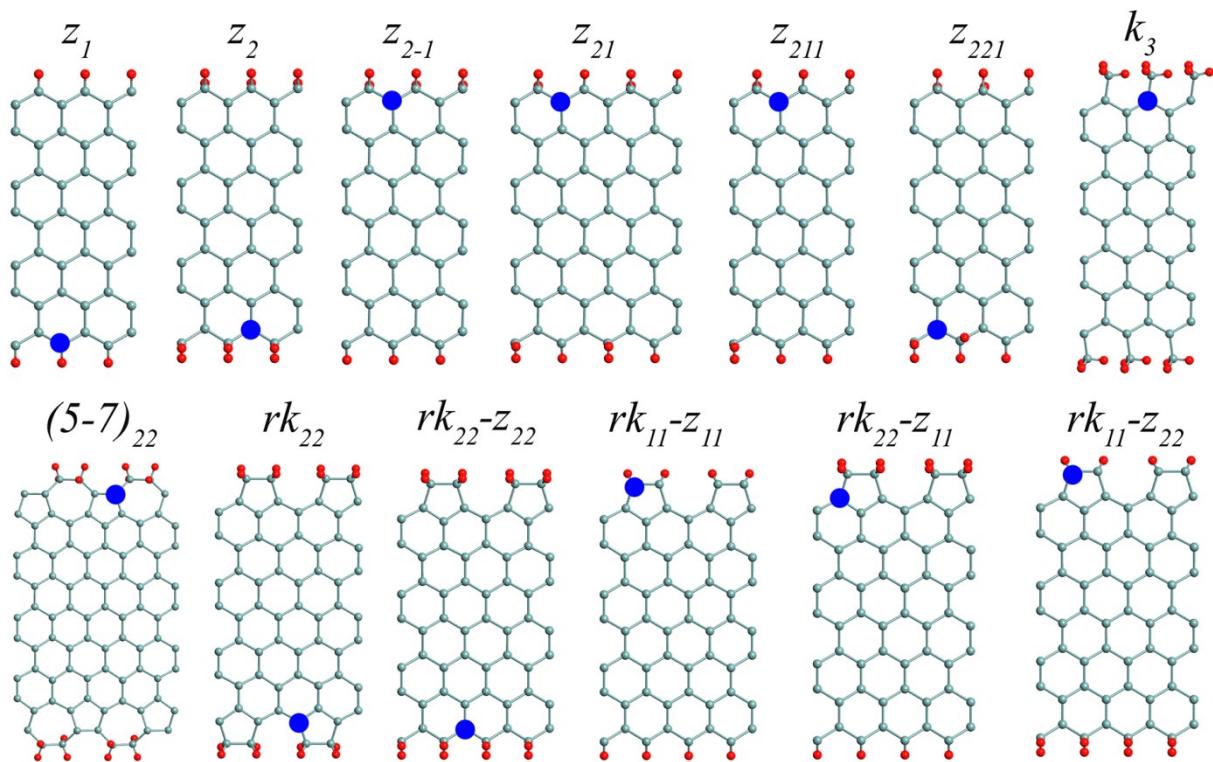


Fig. S3 Different edge structures of functionalized SiNRs along the $<2\bar{1}\bar{1}0>$ direction doped with a N or B atom, in which the most stable substitution configurations are indicated. The cyan and red balls represent Si and functional addends (H, F, Cl, Br, and I), respectively, and the blue solid circle shows a N or B atom.

Table S1 Edge formation energy E_{edge} (eV), band gap E_g (eV), magnetic state, the energy difference between the FM and AFM state $\Delta E_{\text{FM-AFM}}$ (eV), total magnetic moment M_{total} (μB), and spin-polarized band gap (eV) for different armchair edge SiNRs functionalized with hydrogen and halogens.

Edge Type	Edge Atom	E_{edge} (eV/A)	Band Gap (eV)	Magnetic State	Magnetic Edge State		
					ΔE (meV)	Band Gap (eV)	Moment (μB)
a_{11}	Bare	+0.330	0.357 (in)	NM	-	-	-
	H	-0.082	0.581 (d)	NM	-	-	-
	F	-1.032	0.514 (d)	NM	-	-	-
	Cl	-0.433	0.411 (d)	NM	-	-	-
	Br	-0.314	0.218 (d)	NM	-	-	-
a_{22}	I	-0.183	0.201 (d)	NM	-	-	-
	Bare	+0.330	0.357 (in)	NM	-	-	-
	H	-0.129	0.096 (d)	NM	-	-	-
	F	-2.483	0.118 (d)	NM	-	-	-
	Cl	-1.219	0.026 (d)	NM	-	-	-
a_{22-11}	Br	-0.985	0.034 (d)	NM	-	-	-
	I	-0.689	0.109 (d)	NM	-	-	-
	Bare	+0.330	0.357 (d)	NM	-	-	-
	H	-0.025	0.446 (d)	NM	-	-	-
	F	-1.759	0.452 (d)	NM	-	-	-
a_{21}	Cl	-0.822	0.498 (d)	NM	-	-	-
	Br	-0.652	0.558 (d)	NM	-	-	-
	I	-0.439	0.584 (d)	NM	-	-	-
	Bare	+0.330	0.357 (in)	NM	-	-	-
	H	+0.058	0.00	FM-S	-86.55	Up (0.888) (d) – Down (0.697) (in)	1.997
a_{2211}	F	-1.695	0.00	AFM-M	+6.38	0.00	0.00
	Cl	-0.762	0.00	FM-S	-18.12	Up (0.650) (d) – Down (0.55) (in)	1.960
	Br	-0.603	0.00	FM-S	-34.02	Up (0.664) (d) – Down (0.584) (in)	1.790
	I	-0.394	0.00	FM-S	-56.99	Up (0.659) (d) – Down (0.551) (in)	1.990
	Bare	+0.330	0.357 (in)	NM	-	-	-
a_{2211}	H	-0.021	0.334 (d)	NM	-	-	-
	F	-1.749	0.308 (d)	NM	-	-	-
	Cl	-0.761	0.378 (d)	NM	-	-	-
	Br	-0.659	0.397 (d)	NM	-	-	-
	I	-0.446	0.370 (d)	NM	-	-	-

a: armchair, *z*: zigzag, *k*: Klein, *rk*: reconstructed Klein, subscripts: the number of fictional atoms attached to Si edge atom, NM: non-magnetic, FM: ferromagnetic, AFM: antiferromagnetic, S: semiconductor, M: metal, SGS: spin-gapless semiconductor, HF: half-metal, d: direct band gap, in: indirect band gap, ΔE : $E_{\text{FM}} - E_{\text{AFM}}$

Table S2 Edge formation energy E_{edge} (eV), band gap E_g (eV), magnetic state, the energy difference between the FM and AFM state $\Delta E_{\text{FM-AFM}}$ (eV), total magnetic moment M_{total} (μB), and spin-polarized band gap (eV) for different zigzag edge SiNRs functionalized with hydrogen and halogens.

Edge Type	Edge Atom	E_{edge} (eV/A)	Band Gap (eV)	Magnetic State	Magnetic Edge State		
					ΔE (meV)	Band Gap (eV)	Moment (μB)
Z_1	Bare	+0.381	0.00	NM	-	-	-
	H	+0.097	0.00	AFM-S	+5.08	0.313 (d)	0.00
	F	-0.871	0.00	AFM-S	+4.23	0.281 (d)	0.00
	Cl	-0.362	0.00	AFM-S	+4.05	0.271 (d)	0.00
	Br	-0.282	0.00	AFM-S	+4.01	0.269 (d)	0.00
	I	-0.165	0.00	AFM-S	+3.71	0.253 (d)	0.00
Z_2	Bare	+0.381	0.00	NM	-	-	-
	H	-0.101	0.036 (in)	AFM-S	+34.46	0.414 (in)	0.00
	F	-2.064	0.00	AFM-S	+25.44	0.312 (in)	0.00
	Cl	-0.951	0.00	AFM-S	+14.29	0.174 (in)	0.00
	Br	-0.766	0.00	AFM-S	+16.26	0.184 (in)	0.00
	I	-0.469	0.00	AFM-S	+21.39	0.267 (in)	0.00
Z_{2-1}	Bare	+0.381	0.00	NM	-	-	-
	H	+0.053	0.00	FM-S	-12.14	Up (0.540) (d) – Down (0.541) (d)	1.00
	F	-1.460	0.00	FM-M	-8.12	0.00	0.981
	Cl	-0.658	0.00	FM-SGS	-6.17	Up (0.505) (in) – Down (0.277) (in)	0.909
	Br	-0.529	0.00	FM-SGS	-5.99	Up (0.495) (in) – Down (0.273) (in)	0.913
	I	-0.346	0.00	FM-M	-3.20	0.00	0.932
Z_{21}	Bare	+0.372	0.00	NM	-	-	-
	H	+0.002	0.175 (d)	NM	-	-	-
	F	-1.515	0.159 (d)	NM	-	-	-
	Cl	-0.699	0.162 (d)	NM	-	-	-
	Br	-568	0.156 (d)	NM	-	-	-
	I	-0.385	0.156 (d)	NM	-	-	-
Z_{211}	Bare	+0.350	0.00	NM	-	-	-
	H	-0.003	0.160 (d)	NM	-	-	-
	F	-1.698	0.091 (d)	NM	-	-	-
	Cl	-0.786	0.110 (d)	NM	-	-	-
	Br	-0.637	0.109 (d)	NM	-	-	-
	I	-0.431	0.118 (d)	NM	-	-	-
Z_{221}	Bare	+0.383	0.00	NM	-	-	-
	H	-0.402	0.140 (d)	AFM-S	+48.31	0.285 (in)	0.00
	F	-0.648	0.024 (in)	AFM-S	+10.56	0.078 (in)	0.00
	Cl	-0.199	0.025 (in)	AFM-S	+14.47	0.079 (in)	0.00
	Br	-0.152	0.040 (in)	AFM-S	+18.77	0.101 (in)	0.00
	I	-0.085	0.058 (in)	AFM-S	+22.01	0.133 (in)	0.00

a: armchair, z: zigzag, k: Klein, rk: reconstructed Klein, subscripts: the number of fictional atoms attached to Si edge atom, NM: non-magnetic, FM: ferromagnetic, AFM: antiferromagnetic, S: semiconductor, M: metal, SGS: spin-gapless semiconductor, HF: half-metal, d: direct band gap, in: indirect band gap, ΔE : $E_{\text{FM}} - E_{\text{AFM}}$

Table S3 Edge formation energy E_{edge} (eV), band gap E_g (eV), magnetic state, the energy difference between the FM and AFM state $\Delta E_{\text{FM-AFM}}$ (eV), total magnetic moment M_{total} (μB), and spin-polarized band gap (eV) for different Klein edge SiNRs functionalized with hydrogen and halogens.

Edge Type	Edge Atom	E_{edge} (eV/A)	Band Gap (eV)	Magnetic State	Magnetic Edge State		
					ΔE (meV)	Band Gap (eV)	Moment (μB)
k_2	Bare	+0.383	0.00	NM	-	-	-
	H	+0.255	0.00	NM	-	-	-
	F	-1.837	0.00	NM	-	-	-
	Cl	-0.812	0.00	NM	-	-	-
	Br	-0.628	0.00	NM	-	-	-
	I	-0.426	0.00	NM	-	-	-
k_3	Bare	+0.383	0.00	NM	-	-	-
	H	-0.072	0.00	AFM-S	+4.60	0.290 (d)	0.00
	F	-3.237	0.00	AFM-S	+4.55	0.273 (in)	0.00
	Cl	-1.477	0.00	AFM-S	+5.10	0.278 (in)	0.00
	Br	-1.154	0.00	AFM-S	+4.53	0.200 (in)	0.00
	I	-0.763	0.00	AFM-S	+1.01	0.101 (in)	0.00
$k_{33}+z_2$	Bare	+0.334	0.00	NM	-	-	-
	H	-0.103	0.161 (d)	NM	-	-	-
	F	-2.901	0.157 (d)	NM	-	-	-
	Cl	-1.390	0.156 (d)	NM	-	-	-
	Br	-1.103	0.159 (d)	NM	-	-	-
	I	-0.797	0.112 (d)	NM	-	-	-
$(5-7)_{22}$	Bare	+0.354	0.00	NM	-	-	-
	H	-0.020	0.00	NM	-	-	-
	F	-2.076	0.00	NM	-	-	-
	Cl	-0.970	0.00	NM	-	-	-
	Br	-0.372	0.00	NM	-	-	-
	I	-0.288	0.00	NM	-	-	-
rk_{22}	Bare	+0.338	0.00	NM	-	-	-
	H	-0.069	0.00	AFM-S	+8.80	0.281 (d)	0.00
	F	-2.104	0.00	AFM-S	+8.64	0.284 (d)	0.00
	Cl	-1.011	0.00	AFM-S	+8.44	0.275 (d)	0.00
	Br	-0.827	0.00	AFM-S	+8.49	0.276 (d)	0.00
	I	-0.584	0.00	AFM-S	+8.14	0.289 (in)	0.00
$rk_{22}+z_2$	Bare	+0.333	0.00	NM	-	-	-
	H	-0.083	0.160 (d)	NM	-	-	-
	F	-2.120	0.150 (d)	NM	-	-	-
	Cl	-1.014	0.151 (d)	NM	-	-	-
	Br	-0.835	0.141 (d)	NM	-	-	-
	I	-0.588	0.144 (d)	NM	-	-	-

a: armchair, z: zigzag, k: Klein, rk: reconstructed Klein, subscripts: the number of fictional atoms attached to Si edge atom, NM: non-magnetic, FM: ferromagnetic, AFM: antiferromagnetic, S: semiconductor, M: metal, SGS: spin-gapless semiconductor, HF: half-metal, d: direct band gap, in: indirect band gap, ΔE : $E_{\text{FM}} - E_{\text{AFM}}$

Table S4 Edge formation energy E_{edge} (eV), band gap E_g (eV), magnetic state, the energy difference between the FM and AFM state $\Delta E_{\text{FM-AFM}}$ (eV), total magnetic moment M_{total} (μB), and spin-polarized band gap (eV) for reconstructed Klein edge and zigzag edge SiNRs combinations functionalized with hydrogen and halogens.

Edge Type	Edge Atom	E_{edge} (eV/A)	Band Gap (eV)	Magnetic State	Magnetic Edge State		
					ΔE (meV)	Band Gap (eV)	Moment (μB)
$rk_{22-Z_{22}}$	Bare	+0.355	0.00	NM	-	-	-
	H	-0.036	0.00	FM-S	-22.46	Up (0.524) (in) – Down (0.473) (in)	2.003
	F	-2.082	0.00	FM-M	-14.71	0.00	1.607
	Cl	-0.982	0.00	FM-S	-13.26	Up (0.528) (in) – Down (0.270) (in)	1.660
	Br	-0.799	0.00	FM-S	-13.96	Up (0.520) (in) – Down (0.276) (in)	1.875
	I	-0.557	0.00	FM-M	-4.66	0.00	0.492
$rk_{11-Z_{11}}$	Bare	+0.355	0.00	NM	-	-	-
	H	+0.127	0.00	FM-M	-6.94	0.00	0.921
	F	-0.834	0.00	FM-M	-4.04	0.00	1.037
	Cl	-0.329	0.00	FM-M	-4.43	0.00	1.016
	Br	-0.248	0.00	FM-M	-3.67	0.00	1.031
	I	-0.158	0.00	FM-M	-1.21	0.00	1.012
$rk_{22-Z_{11}}$	Bare	+0.355	0.00	NM	-	-	-
	H	+0.015	0.00	AFM-S	+9.5	Up (0.297) (d) – Down (0.301) (d)	0.00
	F	-1.486	0.00	AFM-S	+8.04	Up (0.343) (d) – Down (0.198) (d)	0.00
	Cl	-0.685	0.00	AFM-S	+8.02	Up (0.328) (d) – Down (0.200) (d)	0.00
	Br	-0.554	0.00	AFM-S	+7.94	Up (0.326) (d) – Down (0.201) (d)	0.00
	I	-0.365	0.00	AFM-S	+7.52	Up (0.310) (d) – Down (0.188) (d)	0.00
$rk_{11-Z_{22}}$	Bare	+0.355	0.00	NM	-	-	-
	H	+0.009	0.00	AFM-M	+8.2	0.00	0.00
	F	-1.429	0.00	AFM-M	+6.69	0.00	0.00
	Cl	-0.627	0.00	AFM-M	+2.12	0.00	0.00
	Br	-0.496	0.00	AFM-M	+1.23	0.00	0.00
	I	-0.341	0.00	AFM-M	+0.091	0.00	0.00

a: armchair, z: zigzag, k: Klein, rk: reconstructed Klein, subscripts: the number of fictional atoms attached to Si edge atom, NM: non-magnetic, FM: ferromagnetic, AFM: antiferromagnetic, S: semiconductor, M: metal, SGS: spin-gapless semiconductor, HF: half-metal, d: direct band gap, in: indirect band gap, ΔE : $E_{\text{FM}} - E_{\text{AFM}}$

Table S5 Edge formation energy E_{edge} (eV), band gap E_g (eV), magnetic state, the energy difference between the FM and AFM state $\Delta E_{\text{FM-AFM}}$ (eV), and spin-polarized band gap (eV) for different N- and B-doped armchair edge SiNRs functionalized with hydrogen and fluorine.

Edge Type	Edge Atom	Dopant	E_{edge} (eV/A)	Band gap (eV)	Magnetic State	Magnetic Edge State	
						ΔE (meV)	Band gap (eV)
a_{11}	H	N	-1.005	0.00	FM-S	-0.31	Up (0.137) (in) – Down (0.540) (d)
	H	B	-4.401	0.00	NM	-	-
	F	N	-2.301	0.00	FM-SGS	-0.10	Up (0.092) (in) – Down (0.463) (d)
	F	B	-4.662	0.00	FM-SGS	-0.09	Up (0.481) (in) – Down (0.259) (in)
a_{22}	H	N	-0.683	0.00	NM	-	-
	H	B	-4.412	0.00	NM	-	-
	F	N	-1.170	0.00	NM	-	-
	F	B	-4.662	0.00	NM	-	-
a_{22-11}	H	N	-1.026	0.00	NM	-	-
	H	B	-4.403	0.00	NM	-	-
	F	N	-1.344	0.00	NM	-	-
	F	B	-4.584	0.00	NM	-	-
a_{21}	H	N	-2.067	0.00	FM-S	-170.91	Up (0.310) (d) – Down (0.188) (d)
	H	B	-4.864	0.00	FM-S	-180.46	Up (0.44) (d) – Down (0.630) (in)
	F	N	-1.87	0.00	AFM-S	+43.59	Up (0.248) (in) – Down (0.241) (d)
	F	B	-5.123	0.00	AFM-S	+4.57	Up (0.103) (in) – Down (0.221) (in)

a: armchair, z: zigzag, k: Klein, rk: reconstructed Klein, subscripts: the number of fictional atoms attached to Si edge atom, NM: non-magnetic, FM: ferromagnetic, AFM: antiferromagnetic, S: semiconductor, M: metal, SGS: spin-gapless semiconductor, HF: half-metal, d: direct band gap, in: indirect band gap, ΔE : $E_{\text{FM}} - E_{\text{AFM}}$

Table S6 Edge formation energy E_{edge} (eV), band gap E_g (eV), magnetic state, the energy difference between the FM and AFM state $\Delta E_{\text{FM-AFM}}$ (eV), and spin-polarized band gap (eV) for different N- and B-doped zigzag edge SiNRs and Klein edge SiNRs functionalized with hydrogen and fluorine.

Edge Type	Edge Atom	Dopant	E_{edge} (eV/A)	Band gap (eV)	Magnetic State	Magnetic Edge State	
						ΔE (meV)	Band gap (eV)
z_1	H	N	-1.251	0.00	AFM-S	+0.001	Up (0.161) (d) – Down (0.191) (d)
	H	B	-4.765	0.00	AFM-S	+0.001	Up (0.219) (d) – Down (0.106) (d)
	F	N	-2.699	0.00	AFM-S	+0.009	Up (0.159) (d) – Down (0.155) (d)
	F	B	-5.050	0.00	AFM-S	+0.002	Up (0.198) (d) – Down (0.840) (d)
z_2	H	N	-1.452	0.00	AFM-S	+99.79	Up (0.365) (d) – Down (0.352) (in)
	H	B	-4.598	0.00	AFM-S	+93.55	Up (0.444) (in) – Down (0.243) (in)
	F	N	-2.386	0.00	AFM-S	+5.94	Up (0.131) (in) – Down (0.035) (in)
	F	B	-4.700	0.00	AFM-S	+7.62	Up (0.184) (in) – Down (0.031) (d)
z_{2-1}	H	N	-1.725	0.00	FM-S	-28.43	Up (0.486) (in) – Down (0.200) (in)
	H	B	-4.849	0.00	FM-S	-20.96	Up (0.238) (in) – Down (0.373) (in)
	F	N	-2.416	0.00	FM-HM	-8.42	Up (0.00) – Down (0.174) (d)
	F	B	-4.709	0.00	FM-M	-7.59	0.00
z_{221}	H	N	-2.187	0.00	AFM-SGS	+0.008	Up (0.163) (d) – Down (0.252) (in)
	H	B	-5.508	0.00	AFM-S	+0.007	Up (0.372) (d) – Down (0.111) (d)
	F	N	-2.069	0.00	AFM-M	+0.003	0.00
	F	B	-4.637	0.00	AFM-HM	+0.002	Up (0.238) (in) – Down (0.00)
k_3	H	N	-1.904	0.00	FM-S	-0.010	Up (0.158) (d) – Down (0.170) (d)
	H	B	-5.310	0.00	FM-S	-0.011	Up (0.202) (d) – Down (0.089) (d)
	F	N	-2.682	0.00	FM-S	-0.020	Up (0.149) (d) – Down (0.134) (in)
	F	B	-6.066	0.00	FM-HM	-0.015	Up (0.221) (d) – Down (0.00)
rk_{22}	H	N	-1.171	0.00	FM-S	-0.011	Up (0.129) (d) – Down (0.186) (d)
	H	B	-4.590	0.00	FM-S	-0.020	Up (0.198) (d) – Down (0.072) (d)
	F	N	-1.893	0.00	FM-S	-0.013	Up (0.123) (d) – Down (0.183) (d)
	F	B	-4.648	0.00	FM-S	-0.022	Up (0.203) (d) – Down (0.073) (d)

a: armchair, z: zigzag, k: Klein, rk: reconstructed Klein, subscripts: the number of fictional atoms attached to Si edge atom, NM: non-magnetic, FM: ferromagnetic, AFM: antiferromagnetic, S: semiconductor, M: metal, SGS: spin-gapless semiconductor, HF: half-metal, d: direct band gap, in: indirect band gap, ΔE : $E_{\text{FM}} - E_{\text{AFM}}$

Table S7 Edge formation energy E_{edge} (eV), band gap E_g (eV), magnetic state, the energy difference between the FM and AFM state $\Delta E_{\text{FM-AFM}}$ (eV), and spin-polarized band gap (eV) for N- and B-doped reconstructed Klein edge and zigzag edge SiNRs combinations functionalized with hydrogen and fluorine.

Edge Type	Edge Atom	Dopant	E_{edge} (eV/A)	Band gap (eV)	Magnetic State	Magnetic Edge State	
						ΔE (meV)	Band gap (eV)
$rk_{22}-z_{22}$	H	N	-1.710	0.00	FM-S	-13.660	Up (0.424) (in) – Down (0.383) (in)
	H	B	-4.590	0.00	FM-S	-12.530	Up (0.186) (in) – Down (0.483) (d)
	F	N	-1.893	0.00	FM-S	-13.360	Up (0.479) (d) – Down (0.395) (in)
	F	B	-4.648	0.00	FM-HM	-1.810	Up (0.00) – Down (0.353) (d)
$rk_{11}-z_{11}$	H	N	-1.543	0.00	FM-S	-10.150	Up (0.423) (in) – Down (0.416) (in)
	H	B	-4.522	0.00	FM-M	-0.110	0.00
	F	N	-1.915	0.00	FM-S	-8.230	Up (0.384) (in) – Down (0.423) (d)
	F	B	-5.154	0.00	FM-M	-0.080	0.00
$rk_{22}-z_{11}$	H	N	-0.517	0.00	AFM-M	+0.007	0.00
	H	B	-4.397	0.00	AFM-M	+0.005	0.00
	F	N	-0.999	0.00	AFM-M	+0.002	0.00
	F	B	-4.569	0.00	AFM-M	+0.001	0.00
$rk_{11}-z_{22}$	H	N	-0.556	0.00	FM-S	-12.41	Up (0.320) (d) – Down (0.178) (in)
	H	B	-3.504	0.00	FM-SGS	-6.070	Up (0.082) (in) – Down (0.124) (in)
	F	N	-0.940	0.00	FM-HM	-11.03	Up (0.178) (d) – Down (0.00)
	F	B	-5.199	0.00	FM-HM	-5.84	Up (0.00) – Down (0.307) (d)

a: armchair, z: zigzag, k: Klein, rk: reconstructed Klein, subscripts: the number of fictional atoms attached to Si edge atom, NM: non-magnetic, FM: ferromagnetic, AFM: antiferromagnetic, S: semiconductor, M: metal, SGS: spin-gapless semiconductor, HF: half-metal, d: direct band gap, in: indirect band gap, ΔE : $E_{\text{FM}} - E_{\text{AFM}}$